

ABSTRACT

The present disclosure provides a process chamber of a semiconductor processing device and a semiconductor processing device. The process chamber includes a process chamber body, a base, a protective shield, and a grounding device; the base is movably disposed in the process chamber body, and is configured to support a wafer; the protective shield is disposed around an inner sidewall of the process chamber body, and is configured to protect the inner sidewall of the process chamber body; and the grounding device includes a first connector, a second connector, and a connecting spring, the first connector is connected to the base, the second connector is connected to the first connector through the connecting spring, and the second connector is capable of being attached to the protective shield, so as to electrically connect the base to the protective shield.